

**Amendments to the Specification:**

Please replace the paragraph beginning on page 16, line 1, with the following rewritten paragraph:

In order to avoid that light travels through the thickness of the lamellae without being completely absorbed, the lamellae can be manufactured from a material or a combination of materials that has a sufficiently high absorption of light within the relevant wave length area of 400-700 nm. Absorption of the light in a given material can be described with the following relation:

$$I(t) = I_0 \exp(-\beta \cdot t), \quad (2)$$

wherein  $I(t)$  is the light intensity after having travelled a distance  $t$  through the material,  $I_0$  is the intensity of the light penetrating into the material, and  $\beta$  is the absorption coefficient of the material or extinction coefficient for light in the relevant wave length range. As it has earlier been stated that the thickness ( $T$ ) of the lamellae or generally the distance between the apertures in the raster plate may conveniently be between 10  $\mu\text{m}$  and 100  $\mu\text{m}$ , this means that the raster plate is either manufactured from a material having an absorption coefficient for visible light in the range between the two values given below:

$$\beta > 2,3 \cdot 10^3 \text{ cm}^{-1} \text{ for } T = 10 \mu\text{m},$$

$$\beta > 2,3 \cdot 10^2 \text{ cm}^{-1} \text{ for } T = 100 \mu\text{m},$$

or alternatively that the raster plate is manufactured from a combination of two or more materials that combine to provide sufficient absorption of the visible light across the thickness of the lamella. In case of micro-lamella, this can be accomplished in that the lamellae are constructed around a metal core, since metals effectively absorb all light over a distance of 0.1  $\mu\text{m}$ .

Please replace the paragraph beginning on page 22, line 6, with the following rewritten paragraph:

Figure 10 is a sectional view through a further solar cell 71, wherein it is, however, the counter electrode that is configured as a raster plate corresponding to the plate 31 in Figure 6c. This time, too, it is an nc-DSC solar cell which is, in this case, manufactured by structuring of the counter electrode. As will appear, also the solar cell 71 consists of two halves; a photo-electrode part 72 and a counter electrode part 73, wherein an electrolyte 74 is arranged between the two halves. The manufacture takes its starting point in a transparent substrate 75, eg glass or plastics. This is applied with a thick film of electrically conductive graphite 76 (optionally with an interjacent conductive layer 77 of a transparent material). This can be accomplished by application of a pasta-paste of graphite particles in a suitable suspension, eg butyl acetate or the like. Manufacture of such emulsions on plane substrates is known. Application can be performed by scraping, rolling or the like methods.

Please replace the paragraph beginning on page 28, line 4, with the following rewritten paragraph:

This process takes its starting point in a metal foil, eg 50-75  $\mu\text{m}$  cupper-copper or other metal. The metal is applied on both sides with a layer of photo-active varnish that can be cured by irradiation with ultra-violet rays, X-ray irradiation or the like. This varnish is cured by irradiation through a mesh corresponding to the geometry it is desired to reproduce in the product and the non-cured varnish is removed in accordance with usual procedures in these techniques. Also a reversed process is available, wherein it is the cured varnish that can subsequently be removed; this method is equivalent to the other – the only difference being that it is necessary to radiate through a mesh corresponding to a negative imprint of the desired structure. Following removal of the varnish in selected areas, the exposed cupper

copper surface is removed by etching with a suitable etching agent, whereas that part of the ~~copper~~copper face that is protected by the varnish remains unaltered. Following etching the applied, cured varnish is removed by usual methods, and the pure, patterned ~~copper~~copper structure will appear. This ~~copper~~copper face can subsequently be used as support for a thin-film solar cell of eg CIGS type, wherein the application of the layers in the CIGS cell takes place electrolytically or by usual vacuum-deposition (Chemical Vapour Deposition or Physical Vapour Deposition) methods. The film-solar cell thus produced is subsequently to be laminated onto either glass or plastics. This, too, can be accomplished by usual lamination techniques.

Please replace the paragraph beginning on page 28, line 26, with the following rewritten paragraph:

In the above-mentioned techniques it is an option to use other metals than ~~copper~~, copper, eg silicon; the requirements to be complied with by the metal is that it has to be suitable for the further processing into solar cell, and it has to be able to tolerate chemical process by suitable etching techniques. Likewise, it is of course also an option to employ other thin-film solar cells apart from CIGS, eg amorphous silicon, CdTe or other. The above-described solar cells, wherein photo-electrode or counter electrode are configured as an optical element according to the invention, may, of course, also be manufactured with such controlled, irregular structure.

Please replace the paragraph beginning on page 29, line 13, with the following rewritten paragraph:

A structured photo-electrode can be provided by methods without direct mechanical working in a foaming process of a pasta-paste consisting of TiO<sub>2</sub> particles. The foaming is

provided by mixing TiO<sub>2</sub> particles with a suitable polymer binding system. The mixed substance can be foamed by various methods that are all known techniques for foaming polymer structures, eg admixture of reagent that generates a gas-forming reaction with a polymer component, or by blowing an inert gas into the polymer mixture. The thus foamed substance is spread across a suitable substrate, eg glass with a conductive coating, and the thickness of the thus spread layer is adjusted to the desired thickness of the finished photo-electrode. The spreading can be performed by a rolling with a stationary smooth cylinder or the like known technology. Following curing of the binding agent, it is removed by thermal decomposition and leaves a micro-structured surface that corresponds to the cavities that were originally formed in the foaming process. Due to the surface tension of the liquid, the foaming process will result in the upper layer of the electrode being approximately closed. It is consequently necessary that the uppermost layer of the electrode thus manufactured is removed by a suitable mechanical processing across the entire face, eg by a planing or sanding process.